

ABSTRACT

**Method For Producing A Monocrystalline Layer Of An LNO Material And
5 Substrate For Epitaxial Growth Of A Monocrystalline Layer Of An LNO
Material**

A process for producing a monocrystalline layer of LNO material comprising the
transfer of a monocrystalline seed layer of YSZ material to a carrier substrate of
10 silicon material followed by epitaxial growth of the monocrystalline layer of LNO
material.

Figure 2